Attorney's Docket No.: 14225-009002 / F1020283US01 (KDA 1010019)

Applicant: Kouji Seki et al. Serial No.: 10/770,706 Filed: February 3, 2004

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Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

Listing of Claims:

1-20. (Canceled)

21. (Previously Presented) A semiconductor device manufacturing method comprising: preparing an assembling apparatus comprising a cover, having an opening therein, provided on a setting base comprising a heating function;

setting a plate-like substrate having conductive patterns mounted on the setting base; and mounting a semiconductor chip to the substrate or wire-bonding electrodes of the semiconductor chip to the conductive patterns through the opening,

wherein an illumination is disposed above the opening and a blowing device is provided at a periphery part of the illumination in order to prevent a fluctuation of an inert gas generated by the heating function from entering inside the illumination upon mounting or wire-bonding the semiconductor chip.

- 22. (Currently amended) The semiconductor device manufacturing method of claim <u>21</u> [[15]], wherein the blowing device provides a blow current to escape the fluctuation.
- 23. (Currently amended) The semiconductor device manufacturing method of claim <u>22</u> [[16]], wherein the fluctuation escapes in a horizontal direction.
- 24. (Currently amended) The semiconductor device manufacturing method of claim <u>21</u> [[15]], wherein a part of the cover is formed [[of]] <u>as</u> a clamper.

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- 25. (Currently amended) The semiconductor device manufacturing method of claim <u>24</u> [[18]], wherein the inert gas is blown inside the cover through the clamper.
- 26. (Currently amended) The semiconductor device manufacturing method of claim <u>21</u> [[15]], wherein the inert gas comprises nitrogen gas.
- 27. (Currently amended) The semiconductor device manufacturing method of claim <u>21</u> [[15]], wherein a lens barrel is disposed above the illumination.
- 28. (Previously presented) The semiconductor device manufacturing method of claim 21, wherein a pattern recognition camera is disposed in the lens barrel.
- 29. (New) The semiconductor device manufacturing method of claim 21 wherein the blowing device is located in an area between the illumination and the cover near the opening.